

AZ 9245 – run sheet

AZ Electronic Materials (Clariant AG)

nanyte.com/photoresists/az-9245 · last updated 2026-07-26

Thickness: 4.6–6.6 μm

Softbake: 110 °C · 2 min · hotplate

Exposure dose: 900 mJ/cm²

Develop: Developer AZ 400K Developer · Dilution 1:4 · Time 2 min
· Rinse Spin rinse 300 rpm/20 sec, then spin dry 4000 rpm/15 sec
(following the AZ 400K spray develop at 27°C dispense
temperature). · Method spray